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PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Docket No: Q65210

NAKAMURA, Tsuyoshi, et al.

Appln. No.: 09/901,657

Group Art Unit: 1752

Confirmation No.: 7845

Examiner: Yvette C. Thornton.

Filed: July 11, 2003

For: NOVEL COPOLYMER, PHOTORESIST COMPOSITION, AND PROCESS FOR FORMING RESIST PATTERN WITH HIGH ASPECT RATIO

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OCT 23 2003
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PETITION FOR EXTENSION OF TIME UNDER 37 C.F.R. § 1.136

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

Pursuant to 37 C.F.R. § 1.136, Applicant hereby petitions for an extension of time of three month(s), extending the time for responding to the Office Action of April 16, 2003 to October 16, 2003.

A check for the statutory fee of \$950.00 is attached. The USPTO is directed and authorized to charge all required fees, except for the Issue Fee and the Publication Fee, to Deposit Account No. 19-4880. Please also credit any overpayments to said Deposit Account. A duplicate copy of this sheet is enclosed.

Respectfully submitted,

Bruce E. Kramer

Bruce E. Kramer
Registration No. 33,725

SUGHRUE MION, PLLC
Telephone: (202) 293-7060
Facsimile: (202) 293-7860

WASHINGTON OFFICE
23373
CUSTOMER NUMBER

Date: October 16, 2003